

Supporting information for

Stability and Efficiency Improvement of Perovskite Solar Cells by Surface Hydroxyl Defect Passivation of SnO₂ Layer with 4-Fluorothiophenol

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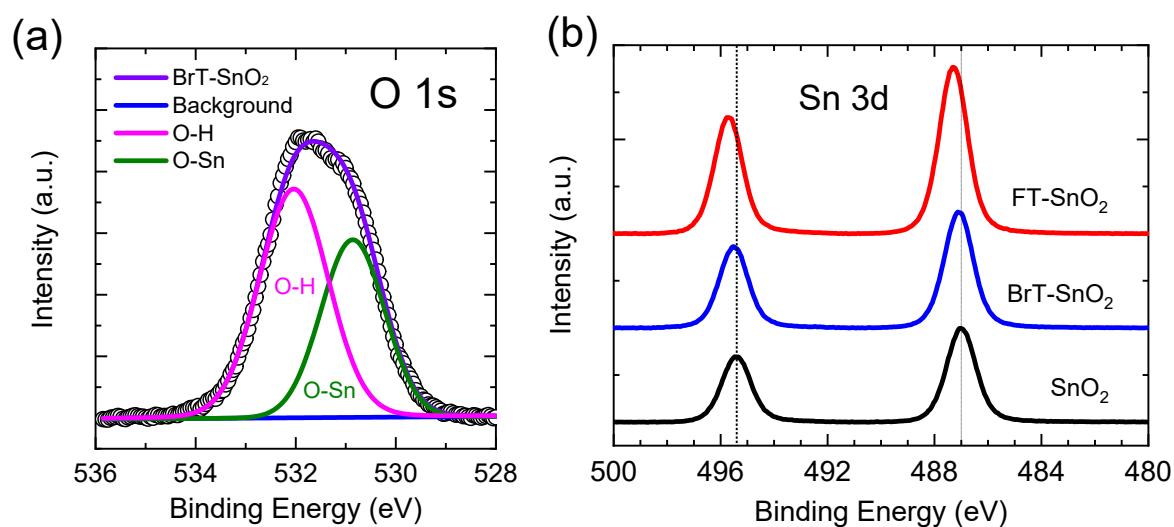


Figure S1. (a) O 1s and (b) Sn 3d XPS spectra for the 4-bromothiophenol treated SnO₂ (BrT-SnO₂).

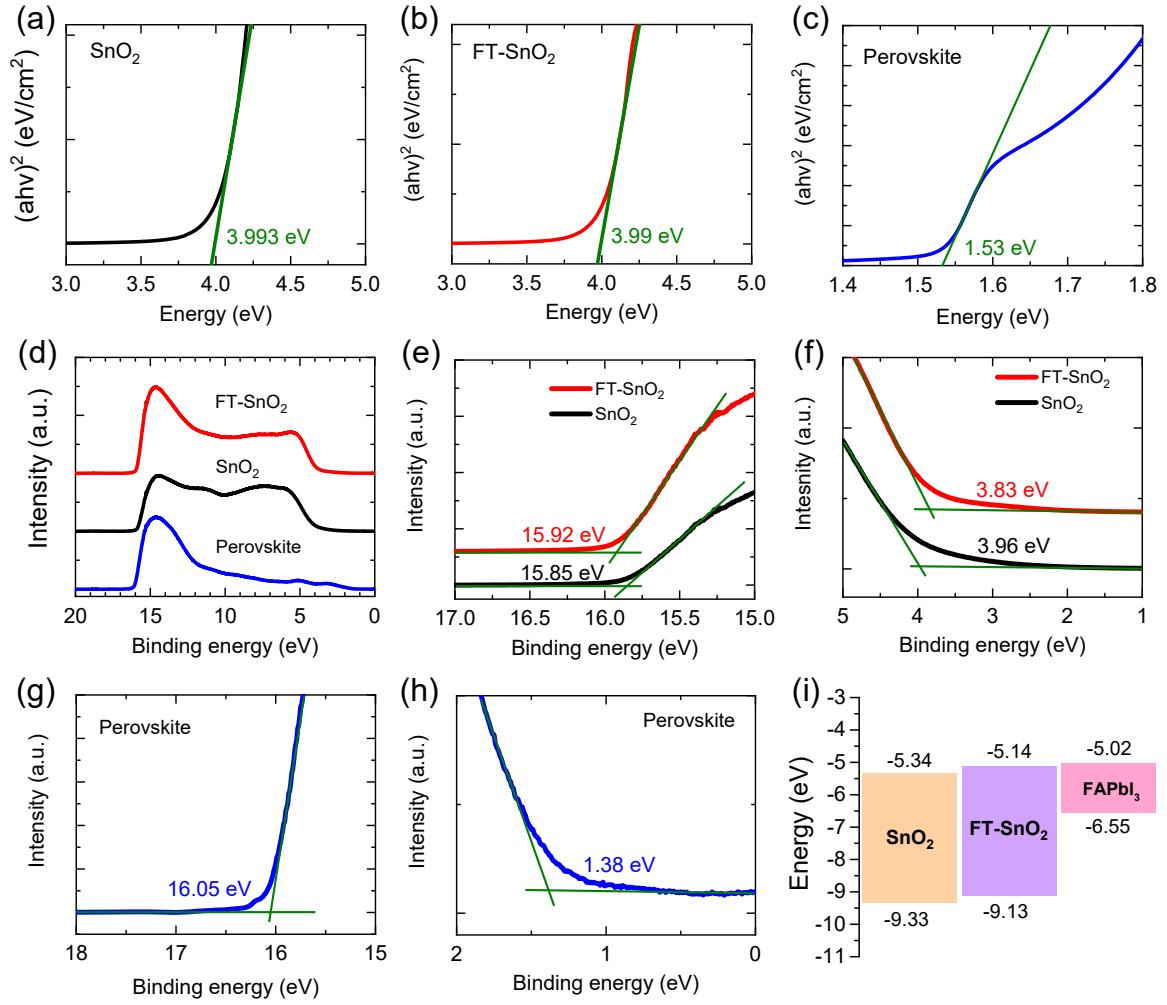


Figure S2. Tauc plots for (a) SnO₂, (b) FT-SnO₂ and (c) perovskite film. Ultraviolet photoelectron spectroscopy (UPS) spectra of (d) SnO₂, FT-SnO₂ and perovskite film coated on Si wafer. (e) Cut-off energy and (f) Fermi edge energy for SnO₂ and FT-SnO₂ film. (g) Cut-off energy and (h) Fermi edge energy for perovskite film. (i) Schematic illustration of energy levels of SnO₂, FT-SnO₂ and perovskite based on the UPS data analysis and band gap energies in Tauc plot.

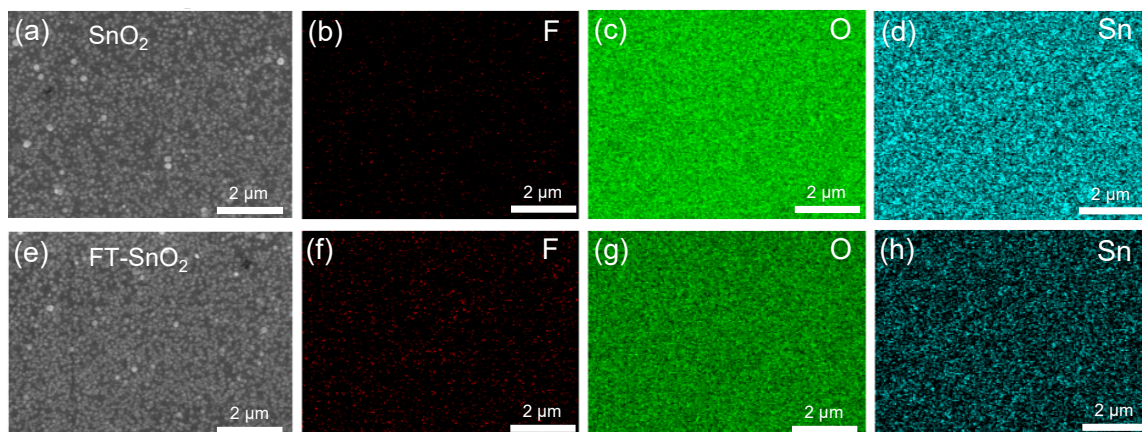


Figure S3. SEM image of (a) SnO₂ and (e) FT-SnO₂ films fabricated on a glass substrate. EDS elemental mapping of (b) fluorine (F), (c) oxygen (O) and (d) tin (Sn) for the bare SnO₂ and (f) F, (g) O and (h) Sn for the FT-SnO₂.

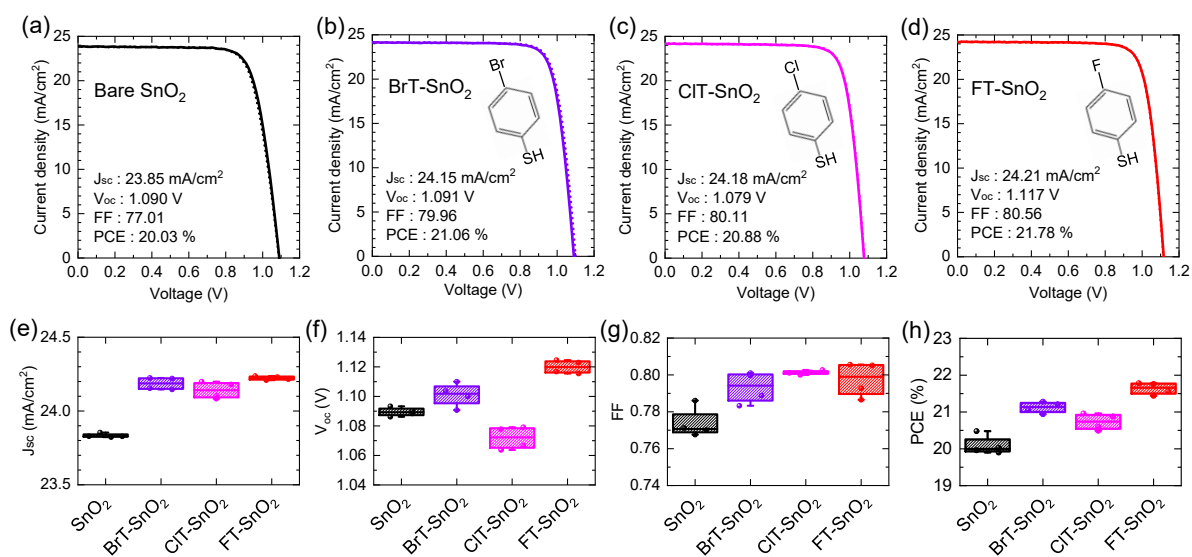


Figure S4. (a-d) J-V curves and (e-h) statistical photovoltaic parameters of J_{sc}, V_{oc}, FF and PCE for the PSCs based on bare SnO₂, BrT-SnO₂, ClT-SnO₂ and FT-SnO₂. Devices were prepared at the same batch. Inset is molecular structure of BrT, ClT and FT.

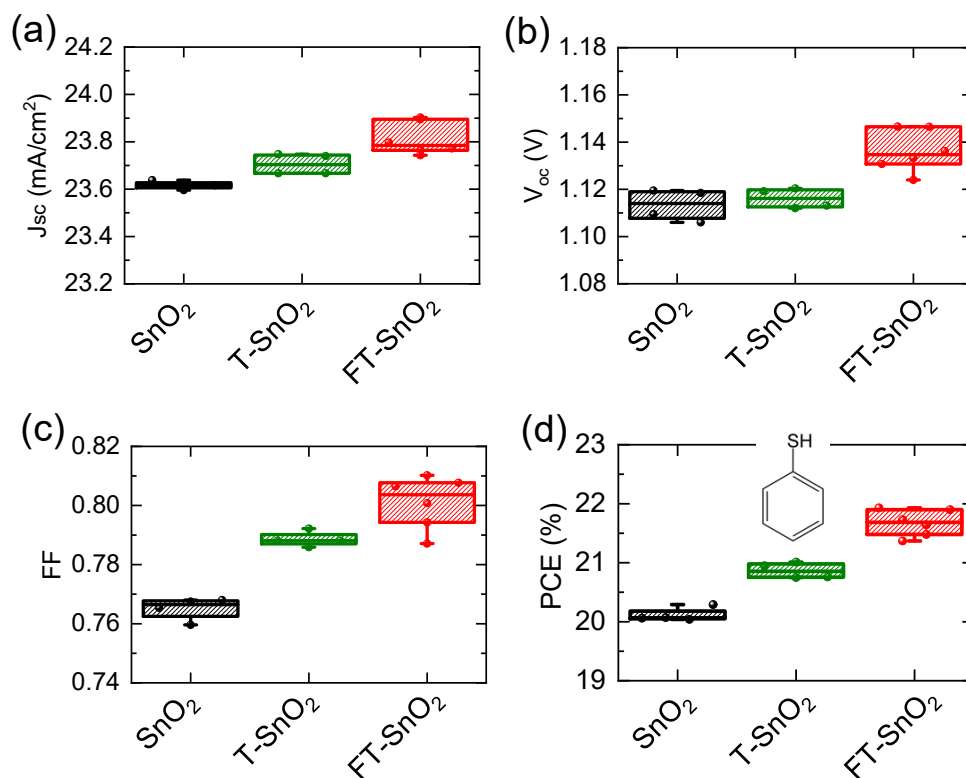


Figure S5. Statistical photovoltaic parameters of (a) J_{sc} , (b) V_{oc} , (c) FF and (d) PCE of the PSCs based on bare SnO_2 , thiophenol-treated SnO_2 (T- SnO_2) and FT- SnO_2 . PSCs were prepared at the same batch.

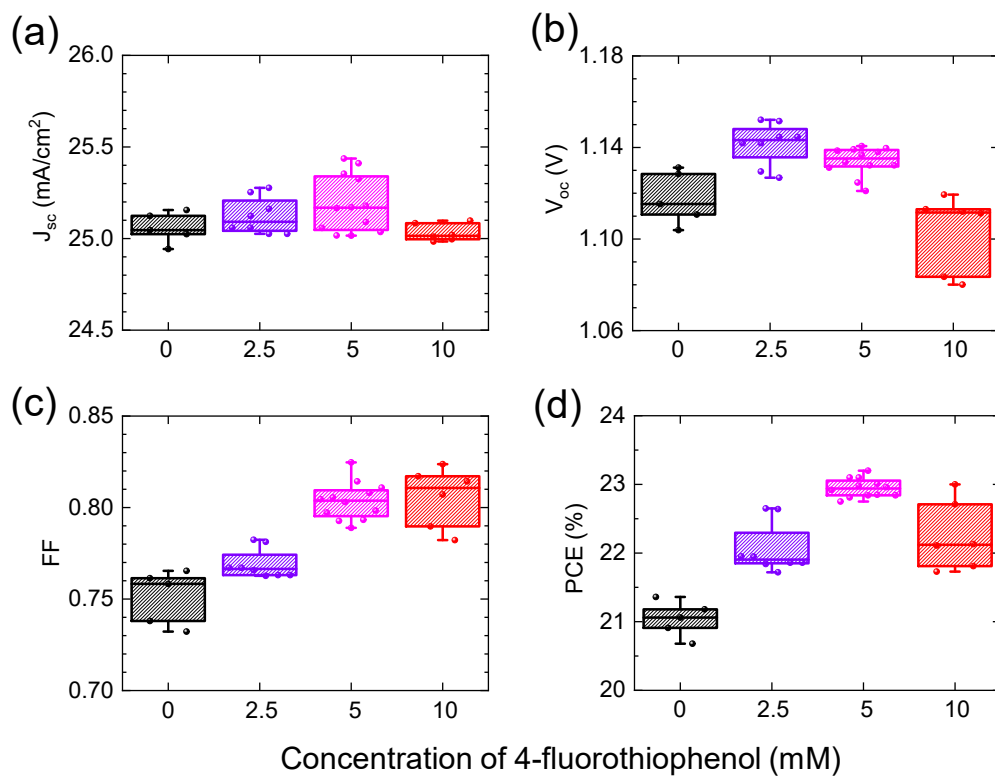


Figure S6. Statistical photovoltaic parameters of (a) J_{sc} , (b) V_{oc} , (c) FF and (d) PCE of the PSCs depending on concentration of 4-fluorothiophenol treated on SnO₂.

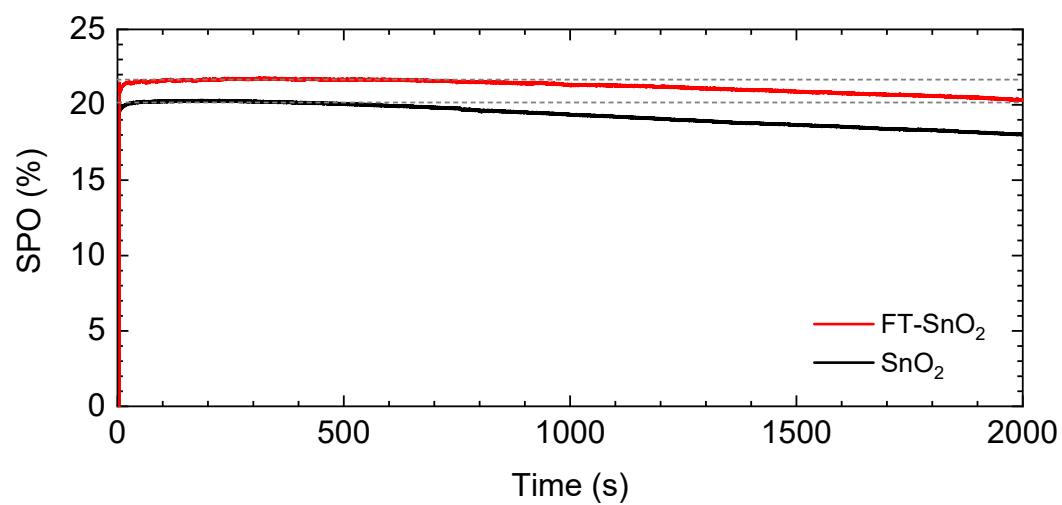


Figure S7. Stabilized power output (SPO) of PSCs based on bare SnO₂ and FT-SnO₂ measured at a maximum power voltage of 0.935 V for bare SnO₂ and 0.951 V for FT-SnO₂, respectively.

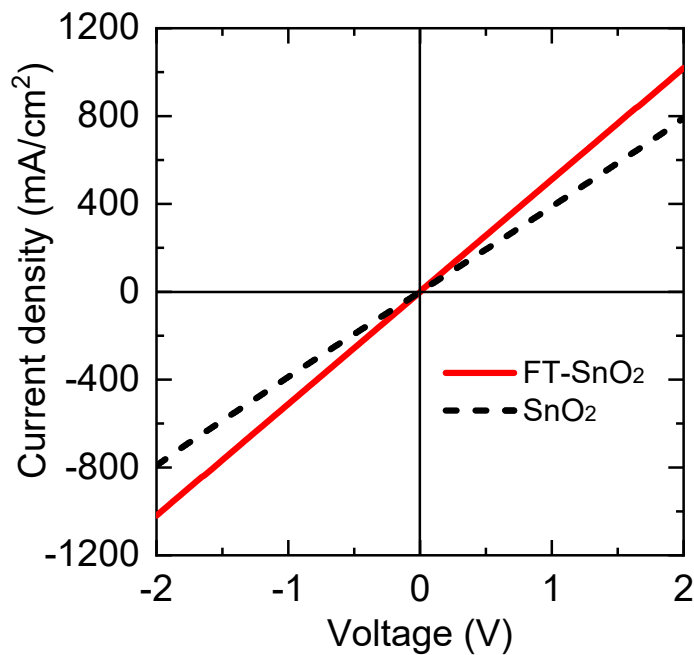


Figure S8. Dark current density-voltage characteristics of devices FTO/SnO₂/Au and FTO/FT-SnO₂/Au.

The conductivity (σ) was calculated by using the equation $\sigma = \frac{d}{A} \times \frac{I}{V}$, where d is the thickness of ETL and A is the active area of film (I and V : current and voltage). The thickness and active area of both SnO₂ and FT-SnO₂ were 40 nm and 0.255 cm², respectively, which led to $\sigma = 1.6 \times 10^{-6} \text{ S/cm}$ and $2.0 \times 10^{-6} \text{ S/cm}$ for SnO₂ and FT-SnO₂, respectively.

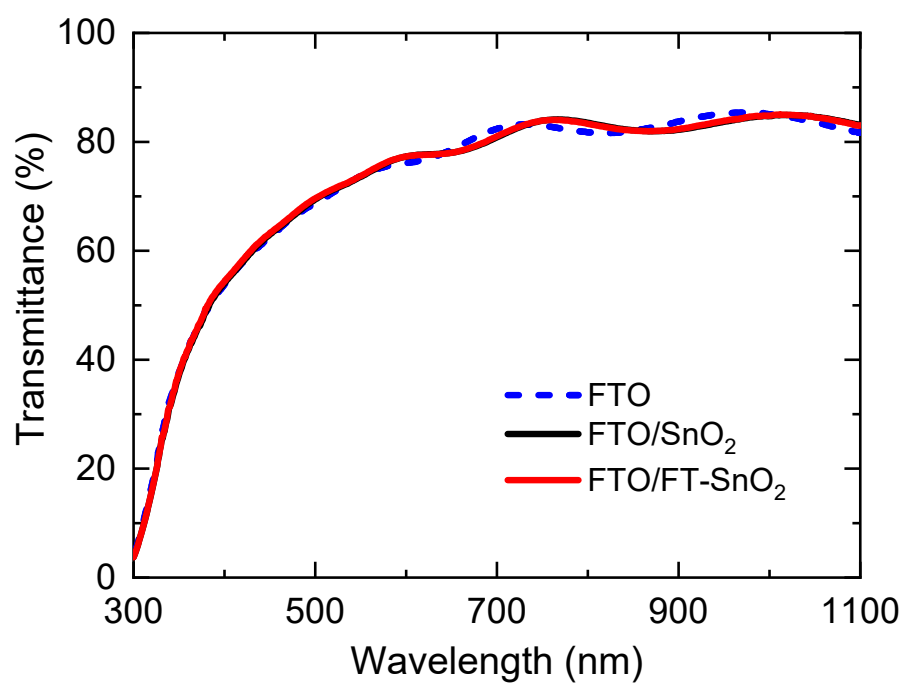


Figure S9. Transmittance spectra for the bare FTO, FTO/SnO₂, and FTO/FT-SnO₂, respectively.

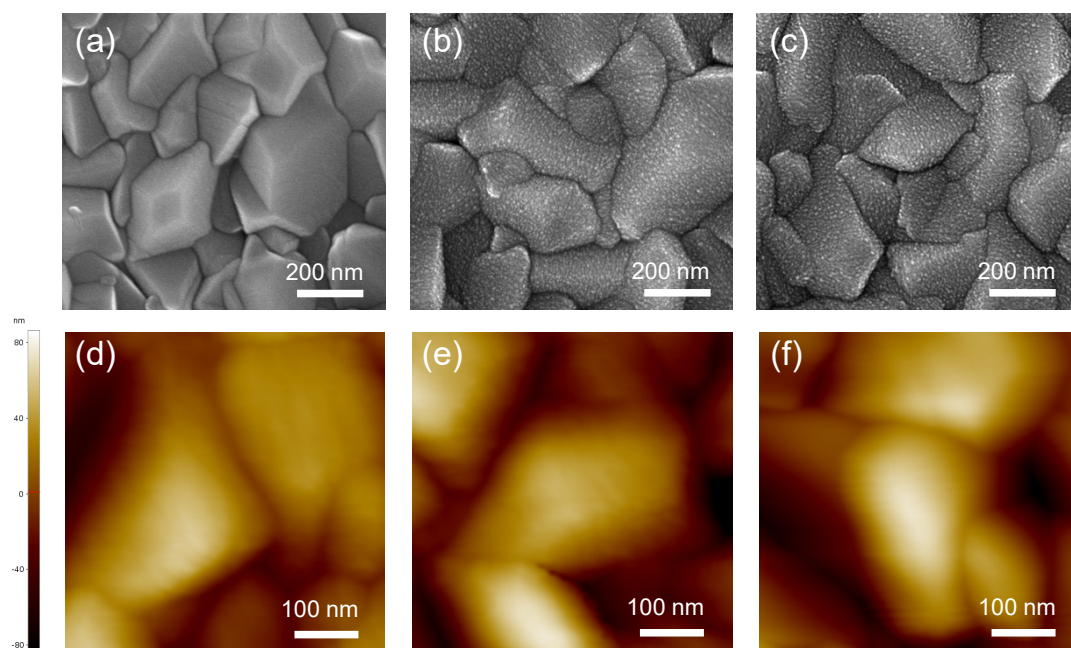


Figure S10. (a-c) Top-view SEM images and (d-f) AFM images of (a) bare FTO, (b) SnO₂ deposited on FTO and (c) FT-SnO₂ deposited on FTO. AFM images were obtained by contact topographic mapping in a scan size of $0.5\ \mu\text{m} \times 0.5\ \mu\text{m}$.

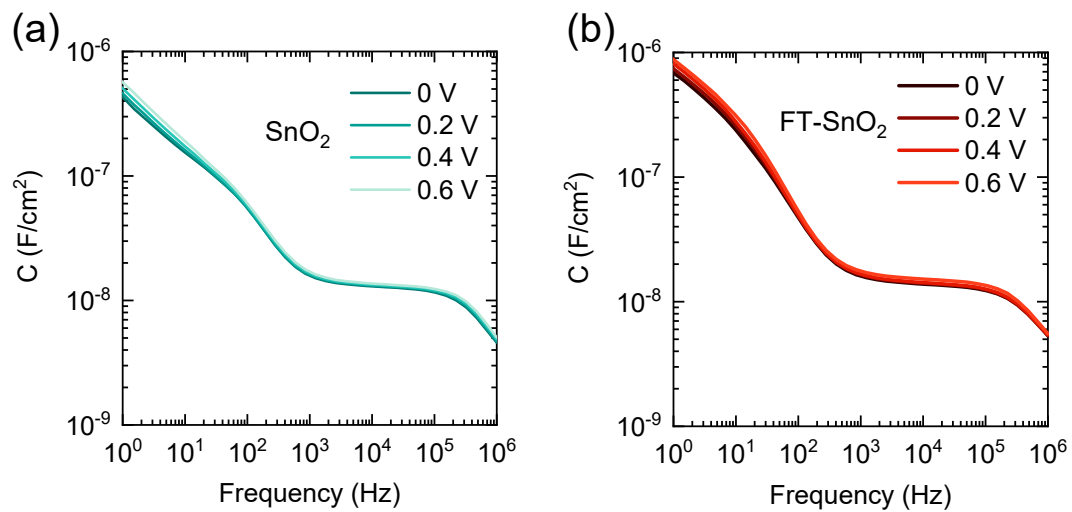


Figure S11. Capacitance-frequency (C-f) plots of PSCs based on (a) SnO_2 and (b) FT-SnO_2 .

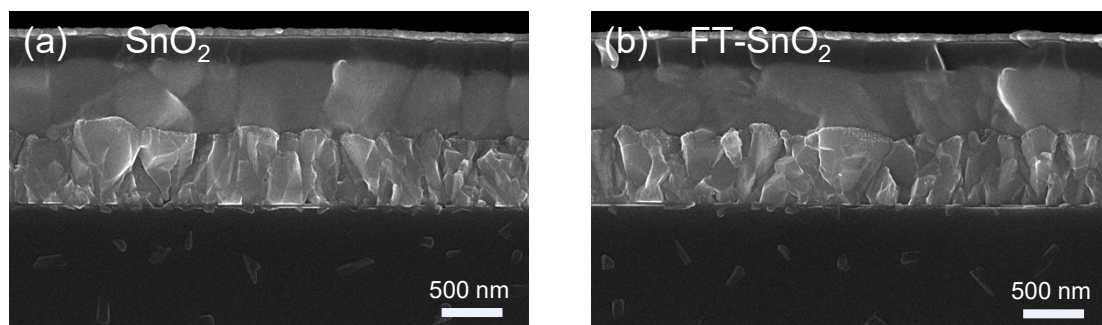


Figure S12. Cross-sectional SEM images of the as-prepared (unaged) PSCs based on (a) bare SnO₂ and (b) FT-SnO₂.

Table S1. Parameters obtained from UPS data and Tau plot for estimating E_{VB} and E_{CB} .

Sample	$E_{cut-off}$ (eV)	E_F (eV)	$E_{F,edge}$ (eV)	E_{VB} (eV)	E_g (eV)	E_{CB} (eV)
SnO ₂	15.85	-5.37	3.96	-9.33	3.99	-5.34
FT-SnO ₂	15.92	-5.30	3.83	-9.13	3.99	-5.14
FAPbI ₃	16.05	-5.17	1.38	-6.55	1.53	-5.02

Table S2. Photovoltaic parameters of PSCs based on the CBD- and spin-coated (SC) SnO₂ before (control, C) and after (target, T) surface modification

SnO ₂ deposition method	Perovskite composition	C/ T	J_{sc} (mA/cm ²)	V_{oc} (V)	FF (%)	PCE (%)	Ref.
CBD	(FAPbI ₃) _{0.95} (MAPbBr ₃) _{0.05}	C	24.5	1.12	81.7	22.4	[1]
		T	24.6	1.16	81.4	23.2	
CBD	Cs _{0.05} (MA _{0.15} FA _{0.85}) _{0.95} Pb (I _{0.85} Br _{0.15}) ₃	C	22.57	1.13	76.94	19.69	[2]
		T	22.95	1.14	80.90	21.24	
SC	(FAPbI ₃) _{0.95} (MAPbBr ₃) _{0.05}	C	23.7	1.08	80.9	20.7	[1]
		T	23.9	1.11	82.0	21.8	
SC	FA _{1-x} MA _x PbI _{3-y} Br _y	C	22.67	1.11	75.86	19.04	[3]
		T	23.37	1.13	80.73	21.39	
SC	Cs _{0.05} FA _{0.81} MA _{0.14} Pb (I _{2.56} Br _{0.44})	C	23.11	1.22	74.69	21.15	[4]
		T	24.20	1.25	76.10	23.06	
SC	FAPbI ₃	C	25.5	1.08	76	21.0	[5]
		T	26.1	1.13	80	23.5	
SC	Cs _{0.05} (FA _{0.83} MA _{0.17}) _{0.95} (I _{0.83} Br _{0.17}) ₃	C	20.7	1.14	66.2	15.6	[6]
		T	23.3	1.17	71.4	19.5	
SC	(FAPbI ₃) _{0.95} (MAPbBr ₃) _{0.05}	C	23.32	1.14	76.5	20.49	[7]
		T	24.42	1.16	80.0	22.84	
CBD	FAPbI ₃	C	25.03	1.11	75.75	21.20	This work
		T	25.28	1.13	80.60	23.09	

Table S3. Average roughness (R_a), and root mean square roughness (R_q) obtained from AFM images of bare FTO, FTO/SnO₂, and FTO/FT-SnO₂ samples.

Sample	R_a (nm)	R_q (nm)
Bare FTO	20.8	25.0
SnO ₂	27.5	32.8
FT-SnO ₂	27.3	32.7

Table S4. Parameters of geometric capacitance (C), trap-filled limited voltage (V_{TFL}), dielectric constant (ϵ) and trap density (n_t).

Sample	C (F)	V_{TFL} (V)	ϵ	area (cm^2)	n_t (cm^{-3})
SnO ₂	1.35×10^{-8}	0.563	34.68	0.255	6.42×10^{15}
FT-SnO ₂	1.44×10^{-8}	0.407	36.99	0.255	4.95×10^{15}

Table S5. EIS parameters of series resistance (R_s), charge transfer resistance (R_{ct}) and CPE for FT-SnO₂ and SnO₂ based PSCs measured at bias of a 0.8V under one sun illumination.

Sample	R_s (Ωcm^2)	R_{ct} (Ωcm^2)	CPE (F)
SnO ₂	16.49	151.5	7.25×10^{-8}
FT-SnO ₂	14.38	139.4	1.90×10^{-7}

References

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